Using NOA81 in microtransfer molding of nanogrooves

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Brain-on-a-chips (BoC) have emerged rapidly in the bioMEMS field to enhance our knowledge of neuro-degenerative diseases and their potential therapeutic interventions.¹⁻³ Recently, we contributed to this field by functionalizing BoCs utilizing replica molding of nanogrooves with a pattern period of 600 nm, ridge width of 230 nm and a height of 100 nm.⁴ Additionally, NOA81 was introduced by us recently as a cost-effective material in the fabrication of microsieve-based BoCs.^{5,6} Aiming to extend our BoC toolbox, here, we apply the PDMS mold making protocol from our previous work⁴ (Figure 1a) for NOA81 microtransfer molding of nanogrooves (Figure 1b-d). Microtransfer molding is known as a variation of soft lithography to assemble a wide range of micro- and nanopatterned materials in 2D/3D spatially organized platforms.⁷ By spin coating NOA81 on the PDMS mold (Figure 1b) at 12000 rpm for 60 s, we created a film of approximately 3 µm thickness, which was partially cured at a UV-dosage of 200 mJ/cm² (Figure 1c). After microtransfer molding the film, for example, onto a microscope glass slide, the assembly was exposed to UV with a dosage of 2000 mJ/cm² before peeling off the PDMS mold (Figure 1c). Finally, the nanogrooves in NOA81 are fully cured with a dosage of 6000 mJ/cm² (Figure 1d). In all three exposure steps the UV lamp was set to an intensity of 15 mW/cm². Atomic force microscopy (AFM) of the PDMS mold and its resulting NOA81 relief, respectively, confirmed the presence of nanogrooves despite a diminished pattern fidelity using the PDMS mold as a reference (Figure 2a-c). The process is also briefly demonstrated for microtransfer molding of nanogrooves to other surfaces, e.g. using a spin coated NOA81 film on a microscope glass cover slip as such type of a substrate (Figure 2c). Additionally, scanning electron microscopy (SEM) provides us with a similar impression (Figure 2d). A detailed analysis of loss in pattern fidelity will be performed next but may solely result from the PDMS mold rather than being related to the material properties of the UVcurable NOA81. In conclusion, using NOA81 in microtransfer molding of nanogrooves will also allow us to introduce such cell guidance patterns onto other bioMEMS substrates in BoCs, like microelectrode arrays.

¹ C. Forro et al., Micromachines **12**, (2021).

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³P. Nikolakopoulou et al., Brain **143**, (2020).

⁴ A. Bastiaens et al., J. Vac. Sci. Technol. B **061802**, (2019).

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Figure 1: Schematic representation of the fabrication process: (a) Replication of nanogroove to PDMS as previously demonstrated by Bastiaens et al.⁴, (b) then to thin NOA81 by spin coating at 12000 rpm. (c) Transfer of nanogroove patterns on glass substrate and UV curing the assembly by 2000 mJ/cm². (d) Removing the PDMS mold and completely cure the assembly by UV light with 6000 mJ/cm².



Figure 2: Nanogroove patterns are visible by the appearing color due to interference and the AFM measurements, respectively. (a) Nanogrooves in PDMS mold. (b) Microtransfer molded NOA81 nanogrooves on a microscope glass slide. (c) Microtransfer molded NOA81 nanogrooves on flat NOA81 substrate. Scale bars:1 cm for a-c. (d) SEM image of the microtransfer molded NOA81 nanogrooves on a flat NOA81 substrate.